

IN SITU ELECTROSTATIC DISCHARGE DEPOLARIZATION  
USING HIGH DENSITY PLASMA

## ABSTRACT OF THE DISCLOSURE

5 A method for electrostatic discharge depolarization is implemented. The buildup of  
charge on tool structures in fabrication tools for semiconductor processing may be expected  
to be of concern whenever high voltage is employed near the structure in a tool. The process  
herein includes selectively exposing the structure to a plasma for a selected time interval.  
10 The duration of the exposure time interval is sufficient to reduce the polarization of the  
structure whereby the forces due to the polarization do not interfere with the transport or  
movement of a wafer being processed.

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